MAR 4 2003 REFERENCES CITED BY APPLICANT

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY DOCKET NO. 219625US99DIV

APPLICANT

SERIAL NO. 10/076,450

Jamal Ramdani et al

1	4 2003	3 2				FILING DATE	<u> </u>	GROUP	
L						February 19, 2002			2815
الرا	MARK	9				U.S. PATENT DOCUMENTS			
Ĭ	EXAMI INITI	INER		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
ŀ	BV		AA	3,802,967	04/09/74	Ladany et al.		02.00	11 / 11 / 10 / 14/12
ŀ	<u>∥() 1√</u>	")	ÁB	4,174,422	11/13/79	Matthews et al.			
ŀ	-		AC	4,404,265	09/13/83	Manasevit			
l			AD	4,482,906	11/13/84	Hovel et al.			· · · · · ·
╟			AE	4,523,211	06/11/85	Morimoto et al.			
ľ			AF	4,661,176	04/28/87	Manasevit		<u> </u>	
l		<u>-</u>	AG	4,793,872	12/27/88	Meunier et al.			
ľ			AH	4,846,926	07/11/89	Kay et al.			
l	-		AJ	4,855,249	08/08/89	Akasaki et al.			
l			ΑI	4,891,091	01/02/90	Shastry			
ľ			AK	4,912,087	03/27/90	Aslam et al.			
l			AL	4,928,154	05/22/90	Umeno et al.			
l			АМ	4,963,949	10/16/90	Wanlass et al.			
ľ			AN	5,141,894	08/25/92	Bisaro et al.			
ľ			AO	5,159,413	10/27/92	Calviello et al.			
ľ			AP	5,173,474	12/22/92	Connell et al.			
ľ			AQ	5,221,367	06/22/93	Chisholm et al.			
l		•	AR	5,225,031	07/06/93	McKee et al.			
Ì	1		AS	5,358,925	10/25/94	Neville Connell et al.			
l			AT	5,393,352	02/28/95	Summerfelt			
ŀ			AU	5,418,216	05/23/95	Fork			
l			ΑV	5,450,812	09/19/95	McKee et al.			
╽			AW	5,478,653	12/26/95	Guenzer		İ	
Ì			AX	5,482,003	01/09/96	McKee et al.			
I			AY	5,514,484	05/07/96	Nashimoto		Ì	
ı	i		AZ	5,556,463	09/17/96	Guenzer			
I	ļ		ВА	5,588,995	12/31/96	Sheldon			
ľ			вв	5,670,798	09/23/97	Schetzina			
I	Ì		вс	5,733,641	03/31/98	Fork et al.			
╽	1		BD	5,735,949	04/07/98	Mantl et al.			
ľ			BE	5,741,724	04/21/98	Ramdani et al.			
			BF	5,810,923	09/22/98	Yano et al.			
			1	5,830,270	11/03/98	McKee et al.			
			вн	5,912,068	06/15/99	Jia			
			BI	6,020,222	02/01/00	Wollesen			
			BJ	6,045,626	04/04/00	Yano et al.			
			вк	6,064,078	05/16/00	Northrup et al.			
			BL	6,064,092	05/16/00	Park			
ľ				6,096,584	08/01/00	Ellis-Monaghan et al.			
				6,103,008	08/15/00	McKee et al.			
				6,136,666	10/24/00	So			
			BP	6,174,755	01/16/01	Manning			
			BQ	6,180,486	01/30/01	Leobandung et al.			

SHEET 2 OF 23

SERIAL NO. ATTY DOCKET NO. Form PTO 1449 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE 219625US99DIV 10/076,450 APPLICANT LIST OF REFERENCES CITED BY APPLICANT Jamal Ramdani et al FILING DATE GROUP 4 4 2003

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		7			U.S. PATENT DOCUMENTS			
-EXA	MINER HAL		DOCUMENT	DATE	NAME	CLASS	SUB	FILING DATE
1//1	MA.	CA	NUMBER 3,766,370	10/16/73	Walther		CLASS	IF APPROPRIATE
15V	עיע	СВ	4,006,989	02/08/77	Andringa			
	L	CC	4,284,329	08/18/81	Smith et al.			
		CD	4,777,613	10/11/98	Shahan et al.			
,	 	CE	4,802,182	01/31/89	Thornton et al.			<u> </u>
	╀	CF	4,882,300	11/21/89	Inoue et al.			
	+-	CG	4,896,194	01/23/90	Suzuki			
	+-	СН	4,999,842	03/12/91	Huang et al.			
		CI	5,081,062	01/14/92	Vasudev et al.			
		CJ CJ	5,155,658	10/13/92	Inam et al.			
		CK	5,248,564	09/28/93	Ramesh			
		CL	5,260,394	11/09/93	Tazaki et al.			
		CM	5,270,298	12/14/93	Ramesh Taddiken			
		CN	5,286,985	02/15/94				
		СО	5,310,707	05/10/94	Oishi et al.			
		CP	5,326,721	07/05/94	Summerfelt			
		ca	5,404,581	04/04/95	Honjo			
		CR	5,418,389	05/23/95	Watanabe			
		cs	5,436,759	07/25/95	Dijaii et al.			
		СТ	5,576,879	11/19/96	Nashimoto		<u> </u>	
		CU	5,606,184	02/25/97	Abrokwah, et al.			
		CV	5,640,267	06/17/97	May et al.			
		cw	5,674,366	10/07/97	Hayashi et al.			
		сх	5,729,641	03/17/98	Chandonnet et al.			
		CY	5,790,583	08/04/98	Но			•
		cz	5,825,799	10/20/98	Ho et al.			
		DA	5,857,049	01/05/99	Beranek et al.			
		DB	5,874,860	02/23/99	Brunel et al.			
_		DC	5,926,496	07/20/99	Ho et al.			
		DD	5,937,285	08/10/99	Abrokwah, et al.			
		DE	5,981,400	11/09/99	Lo		1 7	
		DF	5,990,495	11/23/99	Ohba			
		DG	6,002,375	12/14/99	Corman et al.			
		DH	6,008,762	12/28/99	Nghiem	<u> </u>		
		DI	6,055,179	04/25/00	Koganei et al.			•
	1	DJ	6,107,653	08/22/00	Fitzgerald			· · · · · · · · · · · · · · · · · · ·
	\dashv	DK	6,113,690	09/05/00	Yu et al.	<u> </u>		
	+-	DL	6,114,996	09/05/00	Nghiem	<u> </u>		
	+	DM	6,121,642	09/19/00	Newns	<u> </u>		
	\dashv	DN	6,128,178	10/03/00	Newns			
	_	DO	6,143,072	11/07/00	McKee et al.	-		
		DP	6,184,144	02/06/01	Lo	 	 	
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ATTY DOCKET NO. SERIAL NO. Form PTO 1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE 10/076,450 219625US99DIV OTPE **APPLICANT** LIST OF REFERENCES CITED BY APPLICANT Jamal Ramdani et al FILING DATE GROUP MAR 1 4 2003 February 19, 2002 2815 **U.S. PATENT DOCUMENTS** SXAMINER INTEREST DOCUMENT DATE NAME CLASS SUB FILING DATE IF APPROPRIATE NUMBER CLASS 4,484,332 11/20/84 Hawrylo EΒ 4.815.084 03/21/89 Scifres et al. EC 4,876,219 10/24/89 Eshita et al. 10/16/90 ĒΟ 4,963,508 Umeno et al. ĒΕ 5,060,031 10/22/91 Abrokwah, et al. EF 5,063,166 11/05/91 Mooney et al. EG 05/26/92 ebby et al. 5,116,461 06/30/92 5,127,067 Delcoco et al. EΗ E 5,144,409 09/01/92 Ма 03/08/94 Chapple-Sokol et al EJ 5,293,050 10/18/94 Calviello et al. EΚ 5,356,831 5,391,515 02/21/95 Kao et al. İΕL EМ 5,442,191 08/15/95 Ма EΝ 5,444,016 08/22/95 Abrokwah, et al. ΕO 5.480.829 01/02/96 Abrokwah, et al. EΡ 06/18/96 Oakley 5,528,414 03/25/97 ΙEQ 5,614,739 Abrokwah et al. ER 5,729,394 03/17/98 Sevier et al. Tsu et al. ES 5,731,220 03/24/98 06/09/98 Paoli et al. FT 5,764,676 07/07/98 Yamamoto Eυ 5,777,762 07/07/98 EΥ 5,778,018 Yoshikawa et al. 07/07/98 Tomich ΕW 5,778,116 ΕX 5,801,105 09/01/98 Yano et al. ΕY 5,828,080 10/27/98 Yano et al. 01/12/99 Goossen et al. ΕZ 5,858,814 FΑ 5,861,966 01/19/99 Ortel 03/16/99 =B 5,883,996 Knapp et al. Klee et al. FC 11/30/99 5,995,359 05/02/00 FD 6,058,131 Pan FE 6,137,603 10/24/00 Henmi FF 6,146,906 11/14/00 Inoue et al. 01/16/01 FG 6.173.474 Conrad 01/30/01 Farrell et al. FΗ 6,180,252 12/30/0 4,242,595 Lehovec F١ FJ 4,398,342 08/16/83 Pitt et al. FΚ 4,424,589 01/03/84 Thomas et al. 10/24/89 Gustafson et al. 4,876,208 ΞL 11/84 FΜ 4,482,422 McGinn et al. 05/19/87 FΝ 4,667,088 Kramer 09/20/88 FΟ 4,772,929 Manchester et al. FP 4,841,775 06/27/89 lkeda et al. 4,845,044 07/04/89 FQ Ariyoshi et al.

Form PTO 1449 U.S. DEPARTMENT OF COMMERCE ATTY DOCKET NO. SERIAL NO. PATENT AND TRADEMARK OFFICE 219625US99DIV 10/076,450 **APPLICANT** REFERENCES CITED BY APPLICANT Jamal Ramdani et al **FILING DATE** GROUP February 19, 2002 2815 **U.S. PATENT DOCUMENTS** DOCUMENT DATE NAME CLASS SUB FILING DATE **EXAMINER** INITIAL IF APPROPRIATE NUMBER CLASS 4,868,376 09/19/89 Lessin et al. 4,885,376 12/05/89 GB Verkade GC 4,888,202 12/89 Murakami et al. GD 4,891,091 12/90 Wanlass et al. GE 09/24/91 Hammer 5,051,790 GF 10/08/91 Belt et al. 5,055,445 11/14/92 Nishimura et al. GG 5,081,519 GH 5,143,854 09/01/92 Pirrung et al. GI 5,185,589 02/09/93 Krishnaswamy et al. 5,191,625 03/02/93 Gustavsson GJ GK 5,194,397 03/16/93 Cook et al. $\overline{\mathsf{GL}}$ 5,208,182 05/04/93 Narayan et al. ĞМ 06/01/93 5,216,729 Berger et al. 05/24/94 GN 5,314,547 Heremans et al. GO 5,352,926 10/04/94 Andrews GP 5,356,509 10/18/94 Terranova et al. 12/06/94 Fischer GQ 5,371,734 GR 5,372,992 12/94 ltozaki et al. GS 5,405,802 04/11/95 Yamagata et al. GT 5,442,561 08/15/95 Yoshizawa et al. GU 5,453,727 09/26/95 Shibasaki et al. G۷ 5,466,631 11/14/95 chikawa et al. 12/05/95 Shi GW 5,473,047 12/95 Summerfelt GX 5,473,171 GY 5,479,033 12/26/95 Baca et al. GΖ 5,486,406 01/23/96 Shi 02/13/96 Partin et al. HA 5,491,461 HB 5,492,859 02/20/96 Sakaguchi et al. H 02/27/96 Takeda et al. 5,494,711 HD 5,504,035 04/02/96 Rostoker et al. HE 5,504,183 04/02/96 HF 5,511,238 04/23/96 Bayraktaroglu 04/96 HG 5,512,773 Wolf et al. Ħ 5,515,047 05/07/96 Yamakido et al. 05/14/96 Yamashita et al. H 5,515,810 HJ 5,519,235 05/96 Ramesh 5,549,977 08/96 Jin et al. HΚ 09/03/96 5,551,238 H Prueitt 09/03/96 Н 5,552,547 Shi $\overline{\mathsf{HN}}$ 5,589,284 12/31/96 Summerfelt et al. НО 5,602,418 02/11/97 lmai et al. ΗP 5,633,724 05/27/97 King et al.

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ATTY DOCKET NO. SERIAL NO. U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE Form PTO 1449 219625US99DIV 10/076,450 OIPE **APPLICANT** LIST OF REPERENCES CITED BY APPLICANT Jamal Ramdani et al GROUP **FILING DATE** MAR 1 4 2003 2815 February 19, 2002 **U.S. PATENT DOCUMENTS** CLASS SUB **FILING DATE** DOCUMENT DATE NAME NUMBER **CLASS** IF APPROPRIATE 11/28/00 Krivokapic 6,153,454 ΚВ 6,191,011 02/01 Gilboa et al KC 6,204,737 03/20/01 KD 6,224,669 05/01/01 Yi et al. ΚE 6,225,051 05/01/01 Sugiyama et al. KF 6,241,821 06/05/01 Yu et al. 07/24/01 Gardner et al. KG 6,265,749 11/01 Kencke et al. КH 6,313,486 11/13/01 Tsuzuki et al. ΚI 6,316,832 01/02 KJ 2002/0008234 Emrick KK 3,670,213 06/13/72 Nakawaga et al. 07/05/88 Qureshi et al. ΚL 4,756,007 ΚМ 09/20/88 Hunsperger et al. 4,773,063 KN 5,394,489 02/28/95 Koch 04/11/95 Mehrgardt et al. KO 5,406,202 ΚP 5,528,067 06/18/96 Farb et al. KQ 5,572,052 11/05/96 Kashihara et al. 06/16/98 Ooms et al. KR 5,767,543 ۲S 6,175,497 01/16/01 Tseng et al. KT 6,197,503 03/06/01 Vo-Dinh et al. 06/19/01 Wang et al. ΚIJ 6,248,459 06/26/01 Usui et al. ΚV 6,252,261 ₹W 6,255,198 07/03/01 Linthicum et al. 07/31/01 ee et al. ٧X 6.268.269 09/18/01 Yu et al. ΚY 6,291,319 11/13/01 Nunoue et al. ΚZ 6,316,785 01/29/02 Yoshimura et al. 6,343,171 _B 4,965,649 10/23/90 Zanio et al. .C 6,253,649 05/01 Kawahara et al. 04/01 Allman et al. ם 6,211,096 05/29/01 Fafard et al. LΕ 6,239,449 .F 2001/0013313 08/16/01 Droopad et al. .G 02/06/01 Sone et al. 6,184,044 Mirkarimi et al. 01/04/00 LΗ 6,011,646 5,227,196 07/13/93 ltoh .1 6,150,239 11/21/00 Goesele et al. K 5,441,577 08/15/95 Sasaki et al. ī 07/10/84 Nozawa et al. 4,459,325 07/12/83 -M 4,392,297 Little 09/15/81 4,289,920 Hovel LN 0 01/25/94 5,281,834 Cambou et al. P 4,901,133 02/13/90 Curran et al. Q 5,514,904 05/07/96 Onga et al.

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BMB) MA_	5,553,089	09/03/96	Seki et al.			
0	МВ	5,528,057	06/18/96	Yanagase et al.			
	МС	6,229,159	05/08/01	Suzuki			
	MD	4,748,485	05/31/88	Vasudev			
	ME	4,984,043	01/08/91	Vinal			
	MF	5,754,319	05/19/98	Van De Voorde et al.			
	MG	6,108,125	08/22/00	Yano			
	МН	5,073,981	12/17/91	Giles et al.			
	МІ	5,140,651	08/18/92	Soref et al.			
	MJ	5,610,744	03/11/97	Ho et al.			
	МК	6,362,017	03/26/02	Manabe et al.			
	ML	6,242,686	06/05/01	Kishimoto et al.			
	ММ	5,689,123	11/18/97	Major et al.			
	MN	5,670,800	09/23/97	Nakao et al.			
	МО	5,067,809	11/26/91	Tsubota			
	MP	5,596,205	01/21/97	Reedy et al.			
	MQ	6,175,555	01/16/01	Hoole			
	MR	5 ,357,122	10/18/94	Okubora et al.			
	MS	4,084,130	04/11/78	Holton			
	МТ	6,093,302	07/25/00	Montgomery			
	MU	6,372,813	04/16/02	Johnson et al.			
	MV.	5,608,046	03/04/97	Cook et al.	<u> </u>		
	MW	5,955,591	09/21/99	Imbach et al.			
<u> </u>	MX	6,022,963	02/08/00	McGall et al.	<u> </u>		
	MY	6,083,697	07/04/00	Beecher et al.			
	MZ	5,063,081	11/05/91	Cozzette et al.			
	NA	5,479,317	12/26/95	Ramesh			
	NB	5,306,649	04/26/94	Hebert			-
	NC	5,962,069	10/05/99	Schindler et al.			
	ND	5,541,422	07/30/96	Wolf et al.			
 	NE	5,873,977	02/23/99	Desu et al.			
	NF	5,538,941	07/23/96	Findikoglu et al.			
	NG	6,046,464	04/04/00	Schetzina			
 	NH	6,235,145	05/22/01	Li et al.	<u> </u>		······
	NI	5,610,744	03/11/97	Ho et al.			
	NJ	5,280,013	01/18/94	Newman et al.			·····
	NK	6,348,373 B1	02/19/02	Ma et al.			
	NL	6,339,664 B1	01/15/02	Farjady et al.			
	NM	4,439,014	03/27/84	Stacy et al.			
	NN	4,889,402	12/26/89	Reinhart			
	NO	5,963,291	10/05/99	Wu et al.			
-	NP	6,011,641	01/04/00	Shìn et al.			,,
 	NQ	6,340,788 B1	01/22/02	King et al.			
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	SB	5,395,663	03/07/95	Alferness et al.		-	
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	SD	5,452,118	09/19/95		_	 	
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<u> </u>	SF	6,300,615 B1	10/09/01	Shinohara et al.			
<u> </u>	SG	6,232,910 B1	05/15/01	Bell et al.			
ļ	SH	5,686,741	11/11/97	Ohori et al.		<u> </u>	
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	SM	6,461,927 B1	10/08/02	Mochizuki et al.			
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	SP	5,981,980	11/09/99	Miyajima et al.			
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	TP	5,283,462	02/01/94	Stengel			
	TQ	6,103,403	08/15/00	Grigorian et al.			
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	UB	5,427,988	06/27/95	Sengupta et al.			
	UC	6,297,842 B1	10/02/01	Koizumi et al.			
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			AAN	5-48072	02/26/93	Japan w/English Abstract	×
			AAO	52-88354	07/23/77	Japan w/English Abstract	×
			AAP	54-134554	10/19/79	Japan w/English Abstract	×
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			AAR	61-108187	05/26/86	Japan w/English Abstract	×
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	BAF	WO 01/33585	05/10/01	WIPO			
	BAG	1-102435	04/20/89	Japan w/English Abstract			
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	BAI	02051220	02/21/90	Japan (English Abstract)	1		
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	BAP	0 964 259	12/15/99	Europe			
	BAQ	0 875 922	11/04/98	Europe			
	BAR	61-63015	04/01/86	Japan w/English Abstract			
	BAS	11340542	12/10/99	Japan (English Abstract)			
	BAT	WO 01/37330	05/25/01	WIPO			
	BAU	0 331 467	09/06/89	Europe			
	BAV	WO 00/16378	03/23/00	WIPO			
	BAW	0 926 739	06/30/99	Europe			
	BAX	0 964 453	12/15/99	Europe			
	BAY	5-152529	06/18/93	Japan w/English Abstract			
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	CAD	WO 02/03467	01/10/02	WIPO		
	CAE	0 630 057	12/21/94	EUROPE		
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	CAH	2002-9366	01/11/02	Japan w/English Abstract		
	CAI	EP 0 881 669	12/02/98	Europe		
	CAJ	WO 02/03480	01/10/02	WIPO		
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	CAM	WO 01/04943 A1	01/18/01	WIPO		xx
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	CAO	JP 58-075868	05/07/83	Japan w/English Abstract		-
	CAP	EP 0 993 027	04/12/00	Europe		
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